



S²MARTS
Powered by **NSTXL**

Welcome to the

AWARENESS DAY

for

**Advanced Integration Interconnection &
Fabrication Growth for Domestic SOTA
Radio Frequency Gallium Nitride
(Starry Nite)**

Wednesday, October 19, 2022



Please ensure audio is muted

Administrative Notes



Please ensure your audio is muted unless presenting

NSTXL will be driving the slide deck. Please utilize the “next slide” prompt when you wish to transition

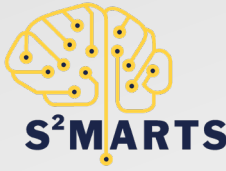
Rules of Engagement

- Be transparent & respectful
- Do not hesitate to ask questions
- If questions arise, please use the raise hand feature

Intent of Session

- Awareness of project objectives and the importance of DIB partners participating through the submission of designs and MPW programs
- Awareness of OSD goals and STARRY NITE’s alignment to those goals
- Understanding of how designs can be submitted through respective foundries and the submission process

Agenda



- 13:00 Opening Remarks by NSTXL
- 13:15 State-of-the-Art Radio Frequency Gallium Nitride Presentation
- 13:30 Application & Submission Process
- 13:45 Northrop Grumman Foundry Process Overview with Q&A (Mike Barsky)
- 14:30 Qorvo Foundry Process Overview with Q&A (Paul Schmid and Marvin Harris will assist with Q&A)
- 15:15 HRL Foundry Process Overview with Q&A (Dave Fanning, Harris Moyer, and Andy Fu will be presenting in that order)
- 16:00 Closing & Wrap-up

STARRY NITE – Industry Day for Designers

State-of-the-Art Radio Frequency Gallium Nitride

Joshua Hawke, Ph.D.

RF & Optoelectronics Execution Lead
OUSD(R&E) Trusted & Assured Microelectronics

Chief Engineer, RF & Optoelectronics
Naval Surface Warfare Center, Crane

19 Oct 2022

Controlled by: OUSD(R&E) Critical Technologies Office
Trusted & Assured Microelectronics Program

Distribution: A

POC: Joshua Hawke,

<https://info.nstxl.org/starry-nite-mpw-program>





Presentation Overview

- OSD Alignment & Goals
- Why RF GaN?
- MPW Program
 - Offerings & Schedule
 - Focus Areas & Trade Spaces
 - How to Apply
 - Deliverables & Data Rights



Program Alignment & Goals

T&AM	Trusted & Assured Microelectronics
RF/OE	Radio Frequency & Optoelectronics
SHIP-RF	State-of-the-Art Heterogeneously Integrated Packaging for RF

• T&AM RF/OE alignment

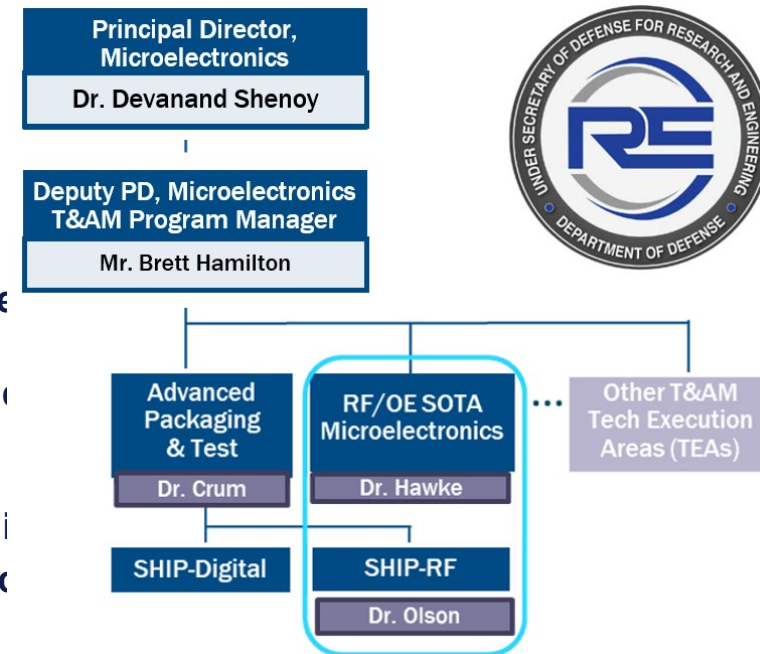
- directly supports OSD's Modernization Priority of Microelectronics
- seeks transition alignment with T&AM Advanced Packaging (e.g., SHIP-RF)

• The RF/OE mission

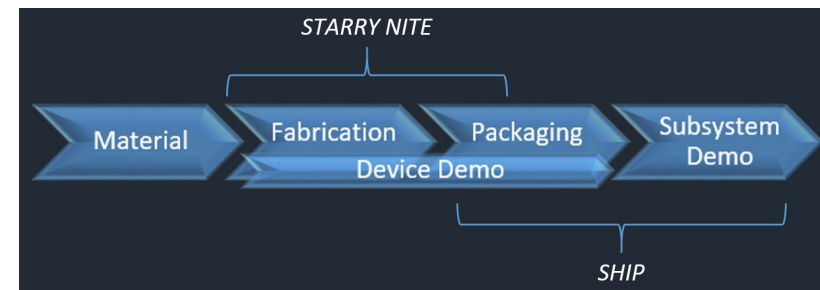
- Develop secure access to state-of-the-art RF GaN and Si Photonic materials, foundries, next generation sensors and communications
- Demonstrate state-of-the-art prototypes and IP, which transition to DoD programs and

• STARRY NITE project goals

- Establish domestic production pilot lines for mmW RF GaN foundries and advanced i
- Offer multi-project wafer (MPW) runs for millimeter wave designers and foster produc Packaging ecosystem.



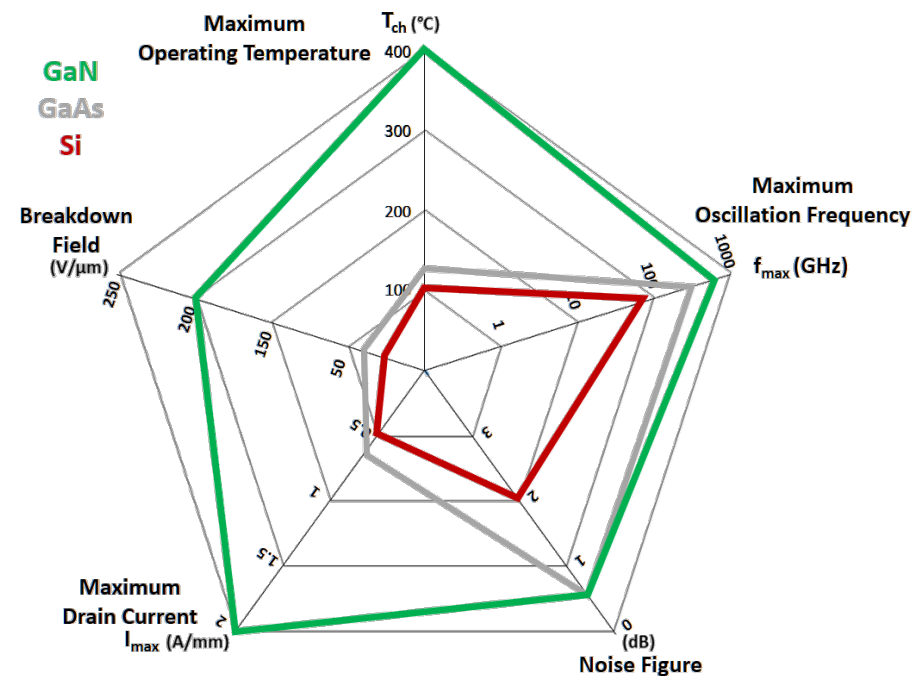
Debuted at Industry Day for Designers





A Case for RF GaN

- RF GaN performance enables critical DoD applications, such as Radar, Electronic Warfare, and Communications
 - High PAE → low loss/cost
 - High power out → smaller sensors/platforms
 - Wide bandwidth → fewer components
 - Ruggedness and radiation hardened → reliability
- Strong dual-use applications, such as 5G, SATCOM, etc.



Drain Current + Breakdown Field → **High Power**

Max Freq + Breakdown Field → **Efficiency**

Max Temp + Breakdown Field → **Robust Operation**



STARRY NITE MPW Program

The STARRY NITE MPW Program...

- Provides domestic designers free MPW space on SOTA RF GaN nodes
 - HRL (40nm T3)
 - Northrop Grumman (90nm)
 - Qorvo (90nm & 150nm)
- Captures designs in a secure IP Repository at each foundry
 - Note: only approved government employees can access the “IP Vault”
- Facilitates transition of designs by inviting top designers to brief transition partners at Defense Industrial Base (DIB) Demo Days
- Does NOT provide stipends for labor, EDA tools, or other expenses associated with design and test
 - Note: this is an ideal opportunity to leverage internal R&D funds and/or cost-share with other DoD-funded design projects



2022 STARRY NITE MPW Schedule

STARRY NITE MPWs			2022		2023												2024		
			Q4		Q1			Q2			Q3			Q4			Q1		
Foundry	Process	Offering	N	D	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M
Qorvo	GaN09	90nm					31												
	GaN15	150nm				28													
	GaN09	90nm		1		1			1								15		
	GaN15	150nm		1		1			1								15		
	GaN15+AIC	150nm															1	1	
NG	GaN09	90nm	10						25										
			18	16			10				25								
HRL	T3 GaN04	40nm		16			31												
			1	1		20													
			22	17					10	9			25						
									2										

Application Due
Nov 1, 2022

Award Announced
Dec 1, 2022

Submit Design
Mar 24, 2023

Receive Die for T&E
Sept TBD, 2023

HRL - 40nm T3

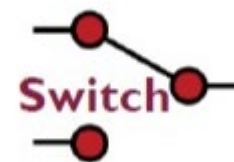
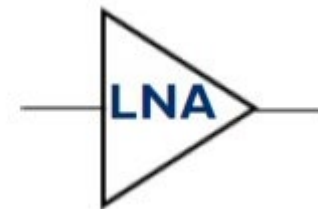
Legend
Application Deadline
Performer Space Awarded
Design Submission
Die Delivered

- 3 Design Focus Areas
 - Radar
 - Electronic Warfare
 - Communications
- DoD Trade Space Interests (see next slides)



GaN-Based RF Components (Examples)

- Power Amplifiers
 - High power added efficiency at higher power
 - Wideband operation
 - Size and weight reduction
- Low Noise Amplifiers
 - Offer low noise and higher input RF power survivability
- Switches
 - High peak power out
 - Can withstand high input power
- Mixers
 - Better linearity and more input power compared to GaAs above S-band

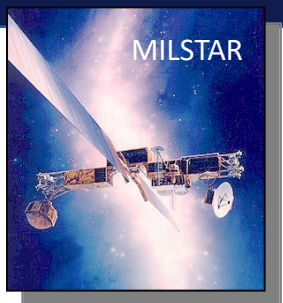




Transmit (Power Amplifiers)

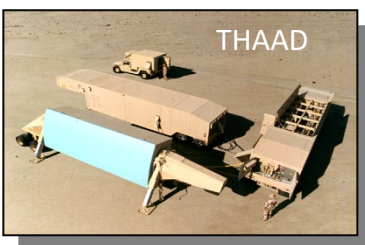
Focus Areas: Radar, EW, and Comm
Trade Space: Power/Efficiency, Frequency, Bandwidth

- Reduced system size, weight, cost
- Manufacturable

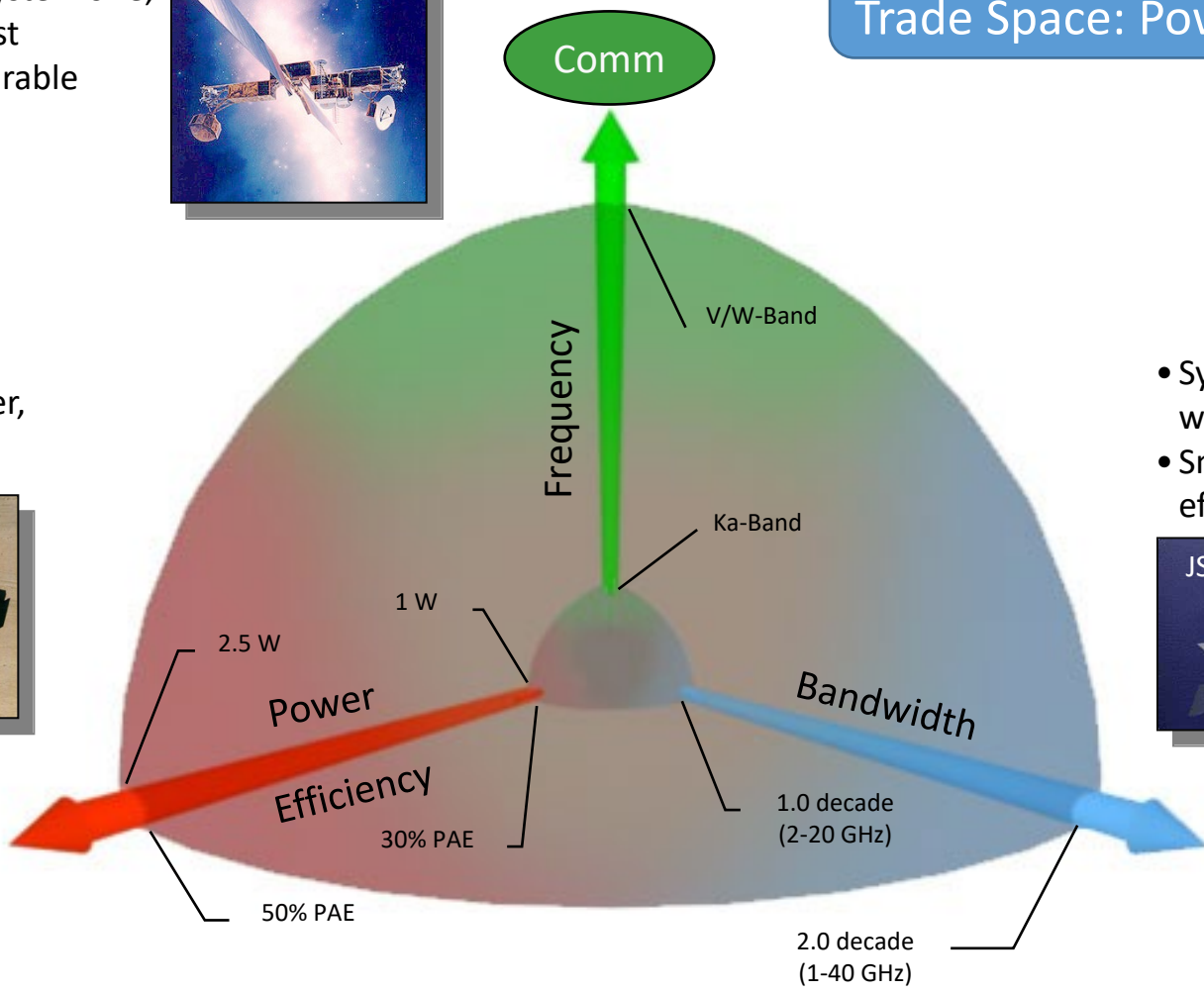


Comm

- Transmit: higher power, reduced cooling



Radar



- Systems that operate over wider bands
- Smaller, lighter, more efficient



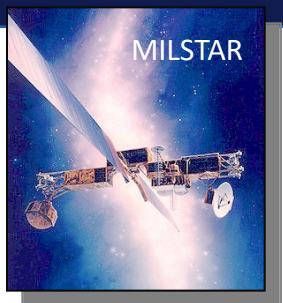
EW



Receive (Low Noise Amplifiers)

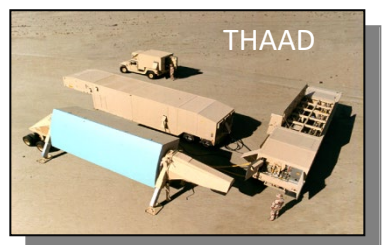
Focus Areas: Radar, EW, and Comm
Trade Space: OIP3/NF, Frequency, Bandwidth

- Reduced system size, weight, cost
- Manufacturable

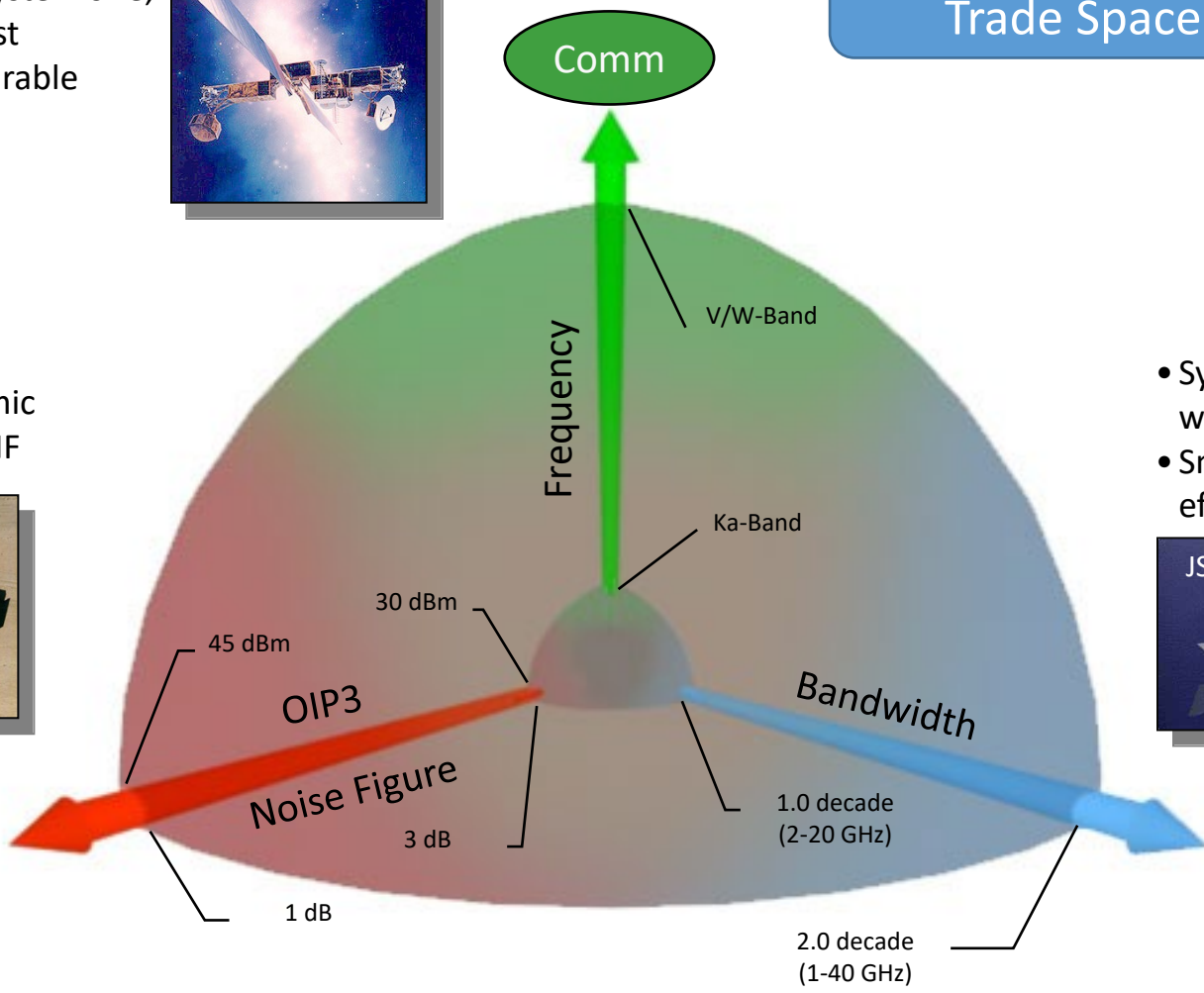


Comm

- Receive: higher dynamic range, lower system NF



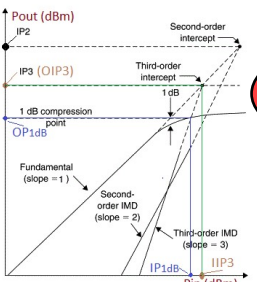
Radar



- Systems that operate over wider bands
- Smaller, lighter, more efficient



EW



[IP3 vs OIP3 | difference between IIP3 and OIP3 \(rfwireless-world.com\)](http://rfwireless-world.com)



How to Apply

Before You Apply

- Review MPW Schedule
- Download Request for Design Application (RFDA)
- Download Industry Day Brief
- Review Design Submission Requirements
- Work NDA with foundry (optional)

To Apply

- Submit completed Application Form to respective foundry prior to application deadline
- Work NDA with foundry (optional)
- Complete PDK training (optional/if available)

If awarded

- Complete the NDA with respective foundry
- Complete Collaboration Agreement with respective foundry
- Complete design by design submission date (i.e., DRC)
- Submit design package to be retained in IP Vault

<https://info.nstxl.org/starry-nite-mpw-program>



Deliverables & Data Rights

	Govt Purpose Rights	Limited Purpose Rights	No Govt Rights
Design Submission Package <ul style="list-style-type: none"> • Circuit layouts in GDS-II • Schematics • Simulation Plots • Information on PDK Version • EDA tools used and version • Any other simulation tools used and version 	Required. Captured as GPR in IP Vault.	Required. Captured as LP in IP Vault	Schematics & Circuit Layouts in GDS-II only. Not in IP Vault.
Post-Design Submission Package <ul style="list-style-type: none"> • Packaged MMICs for IV&V by USG • Raw and summarized test data • Virtual outbrief (see Final Report) 	Preferred/Optional		
Final Report <ul style="list-style-type: none"> • Design & Application • Measured Results vs Simulation • Analysis of PDK & Device Model • Lessons learned for future efforts • Feedback on foundry process 	Preferred/Optional		
DIB Demo Day Pitch <ul style="list-style-type: none"> • Brief on full design of package and evaluation board • Evaluation Board and test code 	Optional upon request		

Notes

- GPR is preferred. Explanations are required in RFDA to select LP or No Govt Rights.
- USG reserves the right to award space to the most competitive proposals.
- Only approved USG employees may access the IP Vault.
- STARRY NITE does not fund labor and materials. Competitive proposals require cost-share (e.g., IRAD).
- Optional tasks intended to facilitate technology transition and provide foundry feedback

Starry Nite Foundry Access at Northrop Grumman

MPW Runs

Mike Barsky
General Manager of
Microelectronics Foundry Services
Northrop Grumman

October 19, 2022

Controlled by: OUSD (R & I)
CUI Category: CTI, PD
Distribution/Dissemination Control: A
Distribution Statement (Pending) Public Release





Outline

- Overview of Northrop Grumman
- Overview of the Microelectronics Foundry at Northrop Grumman
- Overview of the Starry Nite MPW runs with Northrop Grumman
- How to Engage with NG for MPW Runs



Northrop Grumman Today

Leading global security company

\$36.8 billion sales in 2020

– 86% U.S. / 14% International

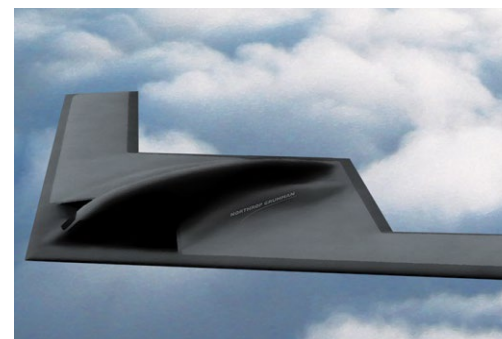
\$81 billion total backlog

(as of Dec. 31, 2020)

~97,000 employees

Leading capabilities in:

- Space
- Missiles
- Advanced Weapons
- Aeronautics
- Mission Systems





Four Operating Sectors at a Glance

Aeronautics Systems



Autonomous Systems

Aerospace Structures

Advanced Technologies and Concepts

Aircraft Design, Integration and Manufacturing

Long-range Strike

Multi-Domain Integration and Operations

Intelligence, Surveillance and Reconnaissance

Battle Management

Defense Systems



Integrated Air & Missile Defense

Defensive Cyber and Information Operations

Platform Modernization and Fleet Operations Support

Advanced Weapons

Precision Munitions

Software Systems Modernization and Sustainment

Training and Simulation

Propulsion Systems

Mission Systems



Airborne Sensors and Networks

Artificial Intelligence/Machine Learning

Cyber and Intelligence Mission Solutions

Navigation, Targeting and Survivability

Maritime/Land Systems and Sensors

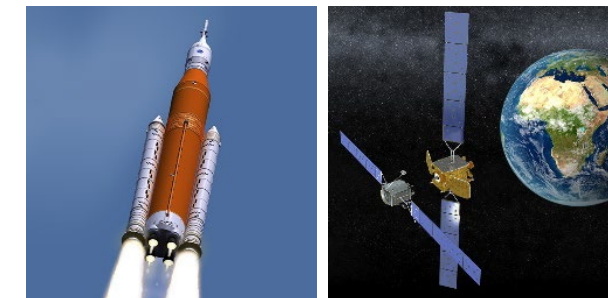
Engineering & Sciences

Emerging Concepts Development

Multi-domain C2

Agile/DevSecOps Systems

Space Systems



Launch Vehicles

Propulsion Systems

Commercial Satellites

Military and Civil Space Systems

Science and National Security Satellites

Human Space and Advanced Systems

Space Components

Missile Defense

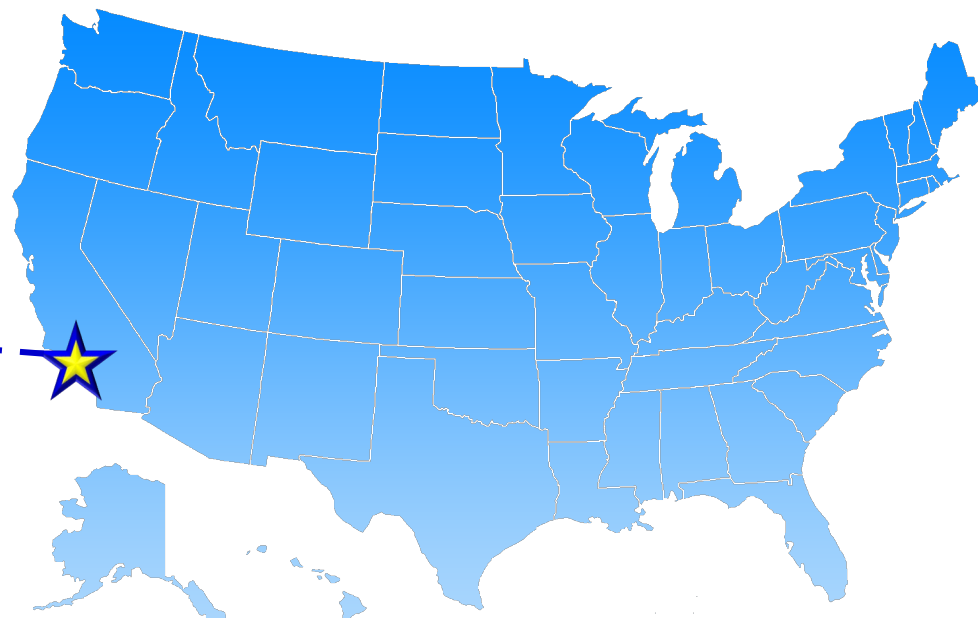
Space Exploration

Space ISR Systems



NG Microelectronics Foundry

Redondo Beach, CA
III-V Facility
GaN Foundry
STARRY NITE

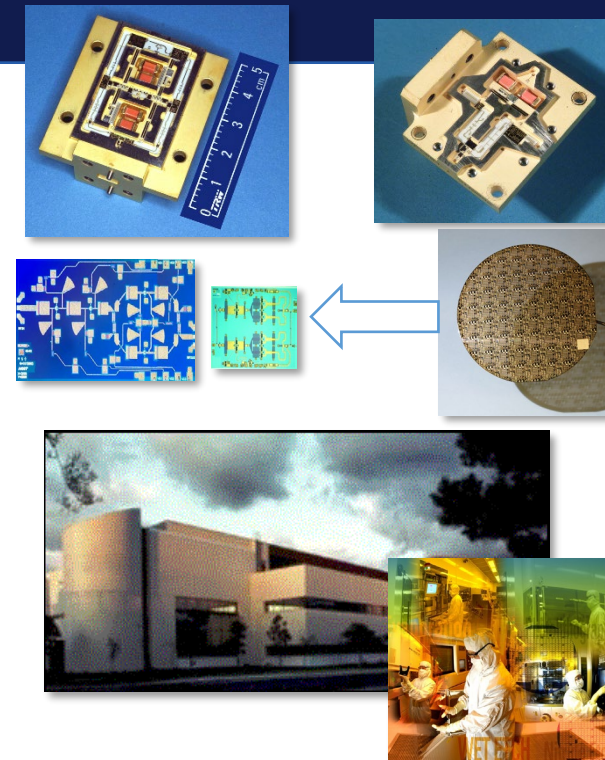


Provide advanced microelectronics capabilities for DoD and commercial products



Microelectronics Products & Services (MPS) Strategic Business Unit Overview

- MPS is the storefront for internal and external access to the Redondo Beach microelectronics and microelectronic-based products
- Product portfolio includes MMIC sales, foundry services and RF unit product developments
- Leverages Redondo Beach-based microelectronics foundry technologies utilized in NG space, airborne and ground products
- NG Space Park foundry:
 - Design/fab/test/qualify MMICs for Space and Commercial applications
 - 100 mm fabrication HEMT (GaAs, InP, GaN), HBT (GaAs, InP) lines
 - Trusted foundry designation
- MPS business predominately operates under fixed price contracts, commercial terms



- Department of Security Services (DSS) Facility Clearance to the SECRET level (Form DD254)
- Certification of SECRET level Networking capability



Foundry Services Technology Offering

- NG Space Park foundry:
 - Design/fab/test/qualify MMICs for Space and Commercial applications
 - 100 mm fabrication HEMT (GaAs, InP, GaN), HBT (GaAs, InP) lines
 - Trusted foundry designation
- NG offers full or shared mask options
- Shared mask is where we divide the wafer into three/four areas for multiple customers

Parameter/ Technology	$f_{T,peak}$ (GHz)	β or G_m	V_{ce}/V_{ds} (V)	Operating Current Density	Wafer Thickness (μ m)	Applications
0.15 μ m GaAs PHEMT	80	550 mS/mm	5	250 mA/mm	50 & 100	<ul style="list-style-type: none"> • High power amps < 5W up to 60GHz • Linear amplifiers • Driver amplifiers • Up/Down converters
0.1 μ m GaAs PHEMT	120	650 mS/mm	4	250 mA/mm	50 & 100	<ul style="list-style-type: none"> • Low noise amplifiers up to 100GHz • Power amplifiers < 1W up to 100GHz • Up/Down converters
1 μ m power InP HBT	80	25	7.5	0.7 mA/ μ m ²	75	<ul style="list-style-type: none"> • Mixed signal designs • ADC/DAC
0.8 μ m digital InP HBT (2met)	160	80	5	1.5 mA/ μ m ²	75	<ul style="list-style-type: none"> • Fiber optic applications up to 25Gbps • High speed digital circuitry
0.6 μ m digital InP HBT (4met)	>250	80	4	2.5 mA/ μ m ²	75	<ul style="list-style-type: none"> • Fiber optic applications up to 40Gbps • High speed digital circuitry
0.1 μ m InP PHEMT	180	1200 mS/mm	1.2	150 mA/mm	75	<ul style="list-style-type: none"> • Very low noise amplifiers • mmW sensors • Lower power dissipation
0.2 μ m GaN HEMT	60	350 mS/mm	28	250 mA/mm	100	<ul style="list-style-type: none"> • High power amplifiers < 10W up to 40GHz
0.15 μ m GaN HEMT	80	410 mS/mm	28	250 mA/mm	100	<ul style="list-style-type: none"> • High power amplifiers < 10W up to 60GHz

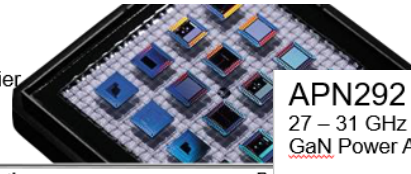


MPS Standard Products (YesWeGaN.com)

GaN Power Amplifiers

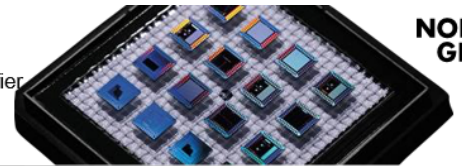
Part	Description	Frequency (GHz)	Gain (dB)	P1 dB (dBm)	Psat (dBm)	Form	Availability
APN267	GaN HEMT Distributed Amplifier	2-18	10	35	38	Die	Stock
APN270	GaN HEMT Power Amplifier	9-13.2	12	39	41	Die	Stock
APN252	GaN HEMT Driver Amplifier	10-14	25.5	34	38	Die	Stock
APN250	GaN HEMT Power Amplifier	10-14	13	39	42	Die	Stock
APN226	GaN HEMT Power Amplifier	13-16	20	36	39.5	Die	Stock
APN232	GaN HEMT Power Amplifier	13.5-15.5	13	38.5	42	Die	Stock
APN237	GaN HEMT Dual Channel Power Amplifier	13.5-15.5	12.5	40.5	44	Die	Stock
APN293	GaN HEMT Power Amplifier	16-20.5	10	36.5	39.5	Die	Stock
APN279	GaN HEMT Power Amplifier	16-20.8	17	39.5	42.5	Die	Stock
APN149	GaN HEMT Power Amplifier	18-23	20	36	39	Die	Stock
APN243	GaN HEMT Power Amplifier	23-28	20	38	40.5	Die	Stock
APN244	GaN HEMT Power Amplifier	23-28	21	37	39	Die	Stock
APN228	GaN HEMT Power Amplifier	27-32	19.5	39	41.2	Die	Stock
APN229	GaN HEMT Power Amplifier	27-32	20	17	39	Die	Stock
APN248	GaN HEMT Power Amplifier	27-31	17.5	42	44	Die	Stock
APN292	GaN HEMT Power Amplifier	27-31	20	42	42	Die	Stock
APN311	GaN HEMT Power Amplifier	27-31	20	43	45	Die	Stock
APN173	GaN HEMT Power Amplifier	34-36	19.5	TBD	37.5	Die	Stock
APN236	GaN HEMT Power Amplifier	34.5-35.5	16	38	40	Die	Stock
APN167	GaN HEMT Power Amplifier	43-46	20	35.5	38.5	Die	Stock
APN318	GaN HEMT Power/Driver Amplifier	47.2-51.4	15	-	40	Die	Pre-Production
APN319	GaN HEMT Power/Driver Amplifier	47.2-51.4	16	-	37	Die	Pre-Production

APN292
27 – 31 GHz
GaN Power Amplifier



NORTHROP GRUMMAN

APN292
27 – 31 GHz
GaN Power Amplifier



NORTHROP GRUMMAN

Revision 2022-1

Absolute Maximum Ratings

Parameter	Value	Unit
Drain Voltage	28	V
Gate Voltage Range	-8 to 0	V
Drain Current	4440	mA
Gate Current	4.32	mA
Power Dissipation*	92.4	W
Soldering Temperature	320	°C

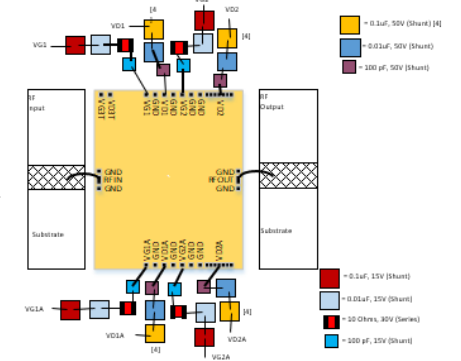
*7W/mm of gate periphery

Electrical Specifications

Parameter	Min
Operational Frequency	27
Small Signal at 28	
Small Signal Linear Gain	19
Input Return Loss	-23.5
Output Return Loss	-15
On-Wafer Pulsed Power	
Psat (at 34 dBm)	45
Power Gain (at 34 dBm)	11
P1db	41.4
PAE (at 34 dBm)	21
Max PAE	26
Fixtured CW at 24V, 25°C C	
Psat (at 29 dBm)	42.7
Power Gain (at 29 dBm)	13.7
PAE (at 29 dBm)	20
Max PAE	21
Drain Voltage	
Stage 1 Gate Voltage	
Stage 2 Gate Voltage	
Stage 1 Idq	
Stage 2 Idq	

Revision 2022-1

Suggested Bonding Arrangement



Recommended Assembly Notes

- Bypass caps should be 100 pF (approximately) ceramic (single-layer) placed no farther than 30 mils from the amplifier.
- Best performance obtained from use of <10 mil (long) by 3 by 0.5 mil ribbons on input and output.
- Part must be biased from both sides as indicated.
- The 0.1uF, 50V capacitors are not needed if the drain supply line is clean. If Drain Pulsing of the device is to be used, do NOT use the 0.1uF, 50V Capacitors.

Mounting Processes

Most NGSS GaN IC chips have a gold backing and can be mounted successfully using either a conductive epoxy or AuSn attachment. NGAS recommends the use of AuSn for high power devices to provide a good thermal path and a good RF path to ground. Maximum recommended temp during die attach is 320°C for 30 seconds.

Note: Many of the NGSS parts do incorporate airbridges, so caution should be used when determining the pick up tool.

CAUTION: THE IMPROPER USE OF AuSn ATTACHMENT CAN CATASTROPHICALLY DAMAGE GaN CHIPS.

PLEASE ALSO REFER TO OUR "GaN Chip Handling Application Note" BEFORE HANDLING, ASSEMBLING OR BIASING THESE MMICs!

MPS also offers standard products in different III-V technologies



Starry Nite Multi-Project Wafer Runs Overview

- As part of the Starry Nite program, open foundry access to NG's 90 nm GaN process is offered through multi-project wafer (MPW) runs

Preliminary Technology Performance Parameters

Technology	f_T (GHz)	f_{max} (GHz)	G_m (mS/mm)	$V_{DS,max}$ (V)	I_{max} (A/mm)	Wafer Thickness (μ m)	Airbridged Metal Available	Backside Vias	Wafer Size (mm)
90 nm GaN HEMT	100	>250	500	15 - 18	1.2	50 μ m	Yes	Yes	100

- The 90 nm GaN process is not a frozen process
- Three model updates are planned during the program
 - 1st updated PDK just released (ADS only)
 - Targeting AWR PDK release for MPW3
- Starry Nite only pays for mask and fabrication
- Designs/Design Package archived into a repository
- Currently offering 5 x 5 mm² space for each awarded design package
- Testing and subdicing available at additional cost through MPS



Starry Nite Multi-Project Wafer Runs Overview

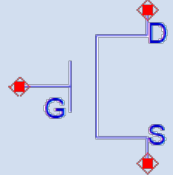
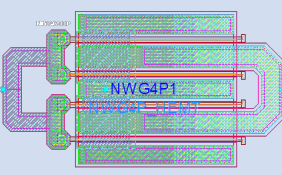



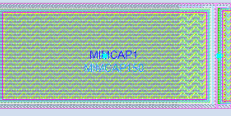

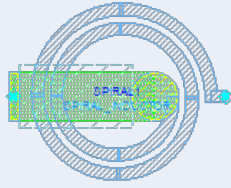
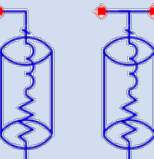
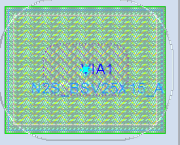
- Wafers will be assessed with passive structures and discrete transistor measurements
- Targeting 30 parts minimum delivered to the performer per MPW design
- Targeting 10 parts minimum delivered to the Government per MPW design

Assessment	Parameter
Transistor	Pinch-off
	maximum drain current
	gate leakage current
	breakdown voltage
	f_T
	maximum available gain
Passive	epi sheet resistance
	ohmic contact resistance
	isolation leakage current
	thin-film resistor sheet resistance
	MIM sheet capacitance



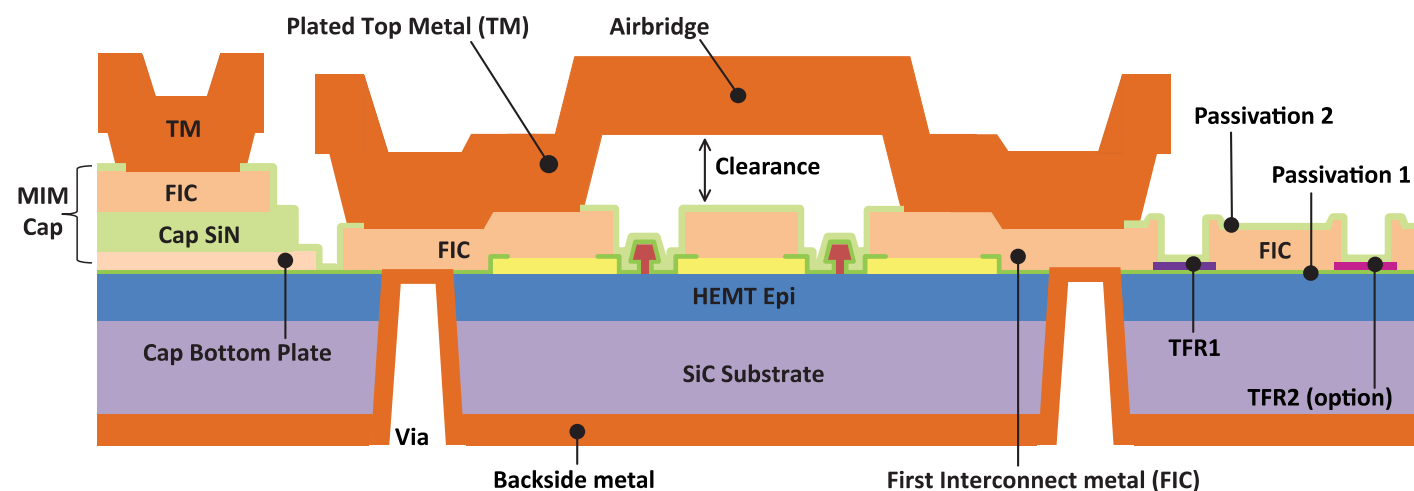
PDK/Model Overview

- Initial PDK in ADS only
 - AWR PDK release by MPW3
- PDK features
 - Schematic capture and simulation
 - Layout generation and EM simulation
 - Models of passives and transistors
 - User adjustable component geometries
 - Design Rule Checking (DRC)
 - Layout Versus Schematic (LVS) check
- NDA required for PDK access

Circuit Element	Schematic Symbol	Layout Cell
Transistors		
Resistors		
Capacitors		
Inductors		
Through-Substrate Vias		

Overview of MMIC Technology

- MMIC process includes
 - Thin film resistors
 - MIM capacitors
 - Through substrate vias (TSVs)
 - Airbridges
 - Spiral inductors





How to Engage with NG for MPW Runs

MPW Application

- Visit NSTXL Starry Nite Webpage
- Decide on desired MPW run from schedule
- Contact Mike Barsky/Farman Mesdaghi to initiate NDA and collaboration agreement
- Download, complete and submit application form to foundry

Performer Space Awarded

- Completed application forms will be reviewed by the government
- NG and government provide award notices

Design Submission

- Completed design and design package submitted to NG
- Mask layout by NG
- Design archived in repository

Die Delivered

- Wafers will be fabricated and cingulated
- Targeting a minimum of 30 parts delivered to designers by mail
- Targeting 10 parts delivered to the government by mail

2022/2023 Starry Nite MPW Runs Calendar

	2022												2023												
	Q1			Q2			Q3			Q4			Q1		Q2		Q3		Q4						
	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M	A	M	J	J	A	S	O	N	D	
MPW1				[Space awarded]									30												
MPW2							[Space awarded]					2						25							
MPW3												18	16				10						25		
MPW4																		12	9				18		
MPW5																								10	8

Application deadline

Space awarded

Design submission

Die delivered

Name	email
------	-------

Mike Barsky mike.barsky@ngc.com

Farman Mesdaghi farman.mesdaghi.@ngc.com

Website: YesWeGaN.com

Qorvo MPW Foundry Offering

STARRY NITE Design Opportunity Day

Qorvo High Performance Analog - Research

October 19, 2022

Controlled by: OUSD (R & I)
CUI Category: CTI, PD
Distribution/Dissemination Control: A
Distribution Statement (Pending) Public Release





Agenda

- Qorvo Overview
 - Qorvo Business Overview
 - Qorvo Foundry Services
 - Qorvo GaN Technology
- Qorvo STARRY NITE Overview
- Qorvo STARRY NITE MPW Runs
 - MPW Overview
 - PDKs
 - Design Space
 - Schedule
 - Design IP Repository
- Q&A



Qorvo Business Overview

Qorvo

A leading global supplier of connectivity and power solutions

- We supply innovative semiconductor solutions that make a better world possible
- 8,900 global employees
- FY22 revenue: \$4.65 billion
- An S&P 500 company – Nasdaq: QRVO





Advancing Technology – Leveraging Dual Use Applications

- Synergy: Each Product Market Benefits the Other

DEFENSE

Provides advanced RF technologies to U.S. DoD and partner countries

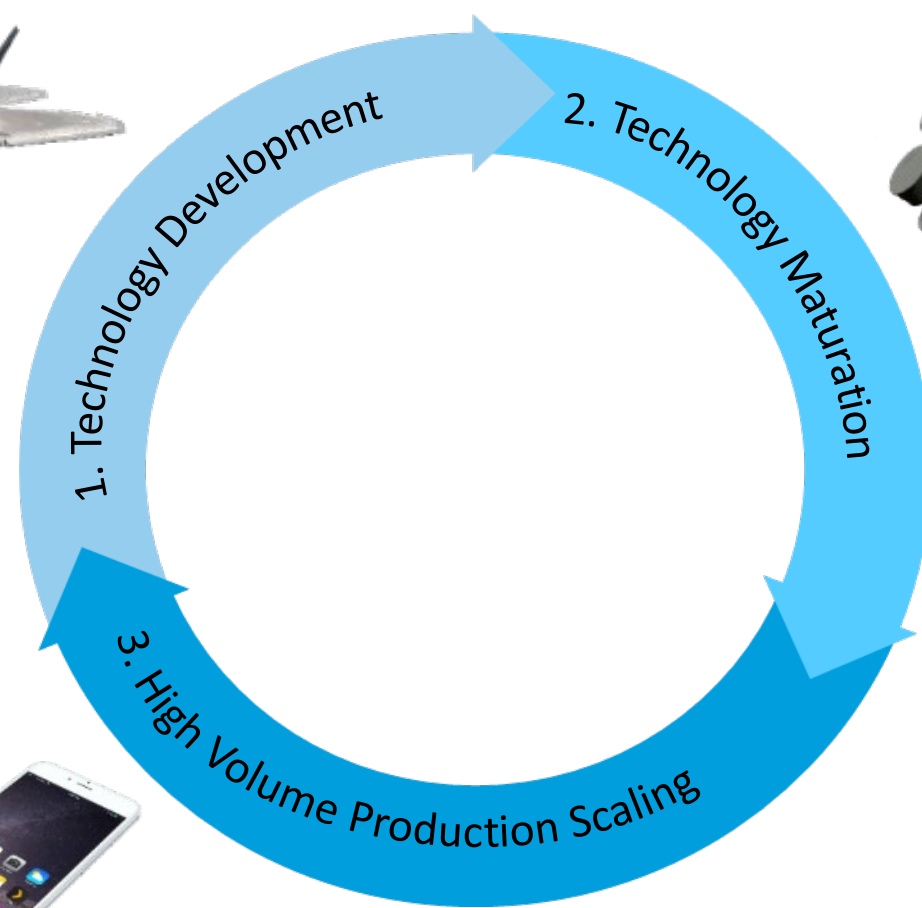


NETWORK INFRASTRUCTURE

Early adopter of RF technology for commercial markets

MOBILE / CONSUMER RF

Provides large manufacturing scale



Qorvo Foundry Services





Qorvo Foundry Services

- Open Access
- Broad and diverse active customer base
 - Services large business, small business, universities, and government labs
- Leading US defense supplier for >30 years
 - Supply to a large cross-section of the defense industrial base
- Large portfolio of GaN / GaAs foundry processes
- Offer early access of advanced & unreleased GaN / GaAs processes to DIB and DoD collaborators
- Trusted CAT1A DoD supplier
- Scale enables cost effective manufacturing – commercial applications drives high volume manufacturing, rapid cycles of learning, improved process control and process maturation

https://www.qorvo.com/foundry

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QORVO all around you

MENU

Entire Site Enter Keyword or Part Number

FOUNDRY

Foundry Services for Strategic Customers

Qorvo's ongoing commitment to innovation extends to our key partners. Qorvo's U.S. based foundry is a critical resource for the DoD and strategic defense primes for developing cutting-edge technology and innovation for mission-critical applications. Our foundry services are centered upon satisfying custom requirements and can blend product and process solutions.

Proven Technology

We offer the largest portfolio of GaN/GaAs foundry processes and advanced packaging expertise to the US DoD. Our portfolio includes world-class industry leading high-performance and high yielding GaN MMIC process ranging from L, S, X, Ku, to Ka band. Qorvo's comprehensive foundry services are complemented by our innovative GaN product solutions, including full MMIC amplifiers, die-level FETs, switches, and wideband transistors from DC-35 GHz.

BENEFITS OF OUR STRATEGIC SERVICES

- Support multiple applications: radar, advanced communications, EW, aerospace
- Provides increased efficiency with shorter lead times
- GaN foundry services support high-power applications and complement our high-frequency standard product portfolio
- In-house highly specialized packaging and integrated assembly facility (AMMA)
- 20+ years expertise packaging and testing high-frequency components
- Products are manufactured with same high-precision process controls that ensure NASA-trusted reliability and functionality

Why Qorvo?

Qorvo's GaN Advantage

Explore Qorvo's GaN Advantage and find out why Qorvo is the smartest choice for your high-quality GaN needs.

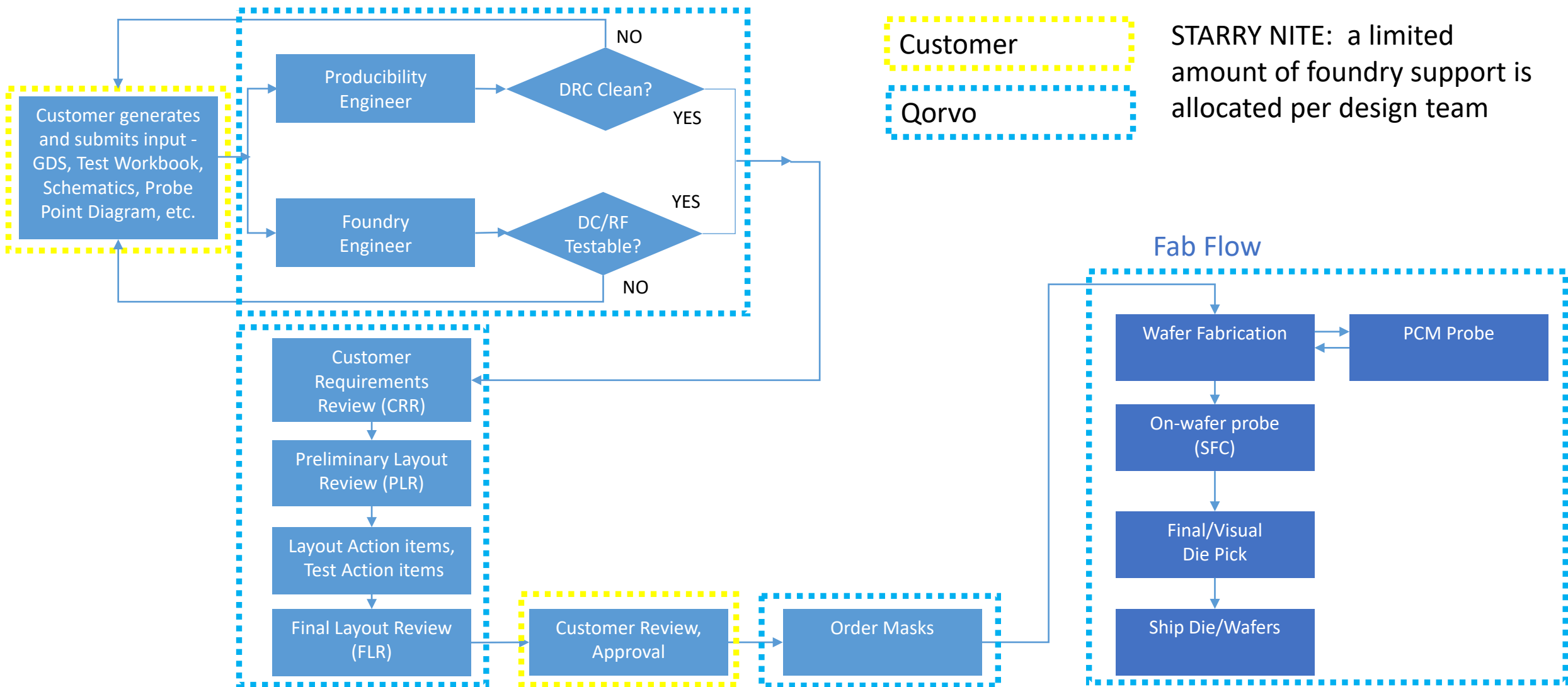
[Explore Qorvo GaN >](#)

< 1 of 3 >

<https://www.qorvo.com/foundry>



Qorvo Texas Fab Typical Foundry Input Flow



Customer
Qorvo

STARRY NITE: a limited amount of foundry support is allocated per design team

Qorvo GaN Technology





Qorvo GaN Technology

- Qorvo has the broadest GaN technology production portfolio in the industry
 - 5 production releases MMIC process nodes supporting applications through 60 GHz
 - Maturing 90nm GaN to support applications in V- and W-band
- Qorvo GaN research and development dates to 1990's
- Qorvo GaN initial production release was QGaN25 in 2008
- Qorvo GaN is deployed worldwide in defense and commercial operations
- Qorvo GaN MMIC processes provide industry leadership in:
 - RF performance
 - Functional integration
 - DC & RF reliability
 - Manufacturing maturity and scalability



Qorvo RF GaN Foundry Processes

	QGaN50-ES	QGaN45-ES	QGaN25 HV-ES	QGaN25-ES	QGaN15-ES	QGaN09-ES
V _{dd}	65V	50V	50 V	40 V	28V	18V
P _{out}	10 W/mm	8 W/mm	8 W/mm	6 W/mm	4 W/mm	2.5 W/mm
Gain	21 dB (2.7 GHz)	20 dB (3.5 GHz)	21 dB (3.5 GHz)	13 dB (10 GHz)	9 dB (35 GHz)	6 dB (80 GHz)
F _t peak	> 20 GHz	> 20 GHz	> 25 GHz	> 35 GHz	> 65 GHz	> 115 GHz
MTTF (200C)	>10 ⁷ h (at 65V)	>10 ⁷ h (at 50V)	>10 ⁷ h (at 50V)	>10 ⁷ h (at 40V)	>10 ⁷ h (at 28V)	>10 ⁷ h (at 18V)
Substrate	100um	100um	100um	100um	100 & 50 um	100 & 50 um
Application Range	DC – 8 GHz	Linear PA DC – 8 GHz	DC – 12 GHz	DC – 25 GHz	DC – 60 GHz	DC – 100 GHz
Status	Production	Production	Production	Production	Production	In Development

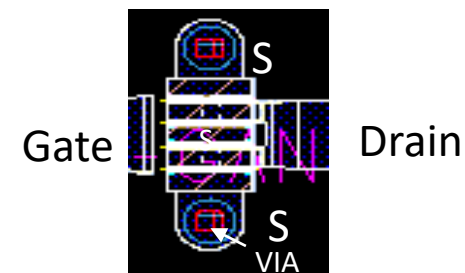


Common GaN Design Feature Set for Production GaN

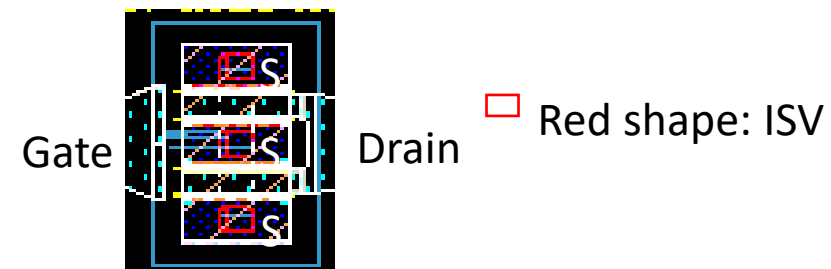
- GaN QGaNxx

- 3 metal layers
- 3 capacitor densities
- 50 μm & 100 μm thick substrates
- With Slot Vias
- XM2 - thick metal
- With or without BCB
- HAST compatible FETs
- Broadside-coupled lines

FET Layout



Conventional End Via



Individual Source Via (ISV)

Qorvo STARRY NITE Objectives





Qorvo's STARRY NITE Scope & Objectives – MPW's

- **Task B:** Offer **MPW runs (15)** and create **Design IP Repository**
 - MPW runs with 3rd party, Govt, and Qorvo designs
 - USG makes the selection of participant designs for each MPW mask run
 - Create a Design IP Repository for USG access
- Total of **15 MPW runs** planned in the program

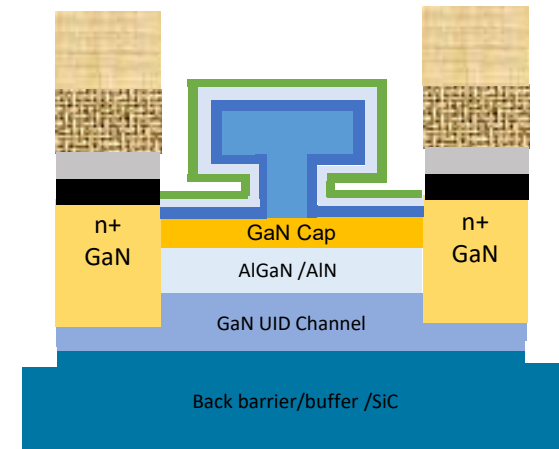
Year (total # of runs)	Year 1 (2)	Year 2 (2)	Year 3 (3)	Year 4 (4)	Year 5 (4)
	CY 2022	CY 2023	CY 2024	CY 2025	CY 2026
Technology (# of MPW runs)	GaN15 (1)	GaN15 (1)	GaN15 w AIC (1)	GaN15 w AIC (2)	GaN15 w AIC (2)
	GaN09 (1)	GaN09 (1)	GaN09 (2)	GaN09 (2)	GaN09 w AIC (2)

- AIC features are added overtime as the maturity occurs with each GaN node
- Each MPW mask to include ...
 - **3 external** party designs
 - At least **1 USG** design
 - At least **1 Qorvo** design

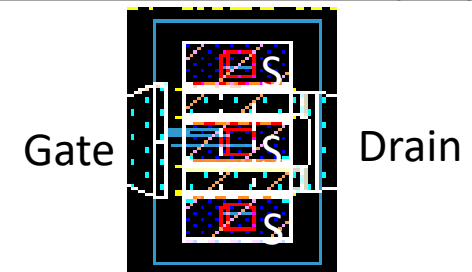


90 nm GaN (QGaN09) Feature Set

- 90 nm GaN technology at MRL-8
 - 150mm wafer diameter on SiC substrates
 - 50 μ m (2-mil) wafer thickness
 - 3 metal interconnect layers
 - 3 capacitor values
 - Full backside processing
 - Individual Source Vias (ISVs)
 - Capable of W-band performance



Individual Source Via (ISV)



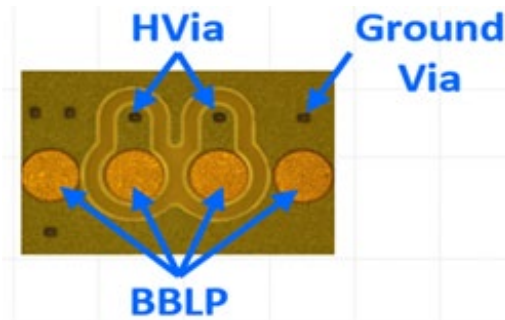
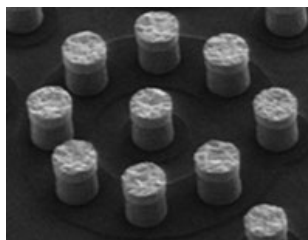
□ Red shape: ISV



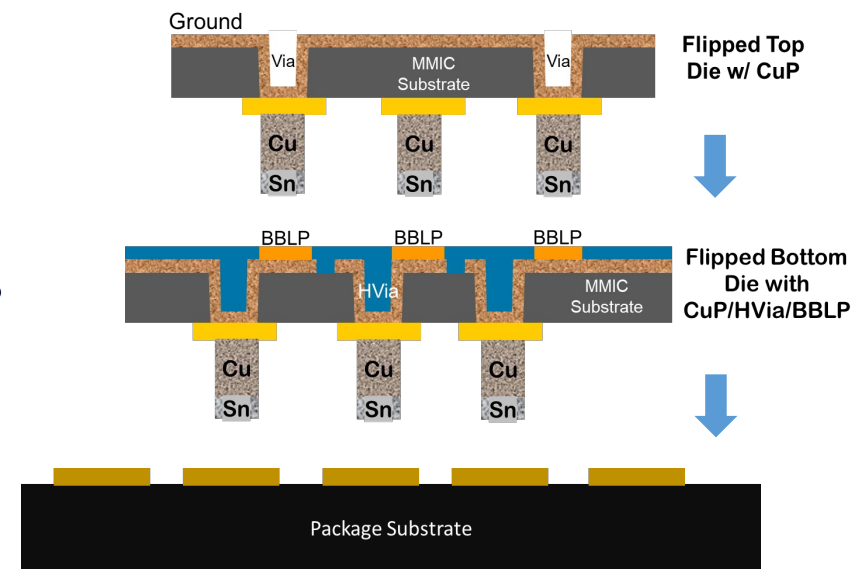
Advanced Interconnect (AIC) Feature Set

- Advanced Interconnect (AIC) features at MRL-8:
 - Two (2) high frequency GaN nodes (90 nm & 150 nm GaN)
 - 150mm diameter wafer production platform
 - 50 μ m (2-mil) wafer thickness
 - Three (3) AIC features are Cu pillars (CuP), Hot Via (HVia), and Backside Bump Landing Pads (BBLP)
 - Enables advanced compact packaging technology for wire bond free 2D/2.5D/3D heterogeneous integration schemes required for high frequency applications

CuP



Example of AIC enabling 2D/2.5D/3D stacking



Qorvo STARRY NITE MPW Runs





Qorvo STARRY NITE MPW Runs – Year 2

- MPW Overall Schedule
- Process Technologies/PDKs
- Design Space
- Schedule, Design Process Flow
 - Key Dates
 - DRC
 - Services/options offered
- Design IP Repository



Qorvo's STARRY NITE MPW – Overall Schedule

Year 1 MPW in Progress

- GaN09 (1run) & GaN15 (1run)
- Design submission Aug '22
- Tape out Oct '22
- Die delivery Mar & Apr '23

Year 2 MPW Plan

- GaN09 (1run) & GaN15 (1run)
- Application CY22 Q4 (Oct – Dec)
- Designer selection CY23 Q1 (Feb)
- Design submission CY23 Q2 (May)

Qorvo			2022				2023				2024				2025				2026																																											
STARRY NITE MPW Offerings			Q1		Q2		Q3		Q4		Q1		Q2		Q3		Q4		Q1		Q2		Q3		Q4																																					
SN Year	Process	MPW#	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M	A	M	J	J	A	S	O	N	D	J	F	M	A	M	J	J	A	S	O	N	D
Year1	GaN09	Run1			22	31																																																								
	GaN15	Run2			22	31																																																								
Year2	GaN09	Run3																																																												
	GaN15	Run4																																																												
Year3	GaN15+AIC	Run5																																																												
	GaN09	Run6																																																												
	GaN09	Run7																																																												
Year4	GaN15+AIC	Run8,9																																																												
	GaN09	Run10,11																																																												
Year5	GaN15+AIC	Run12,13																																																												
	GaN09+AIC	Run14,15																																																												

Legend

sollicitation date
application deadline
performer space awarded
design submission
mask ordered
die delivered

Estimated schedule dates for MPW's by year ... subject to change



Year 2 MPW - Qorvo Process Technologies/PDKs available

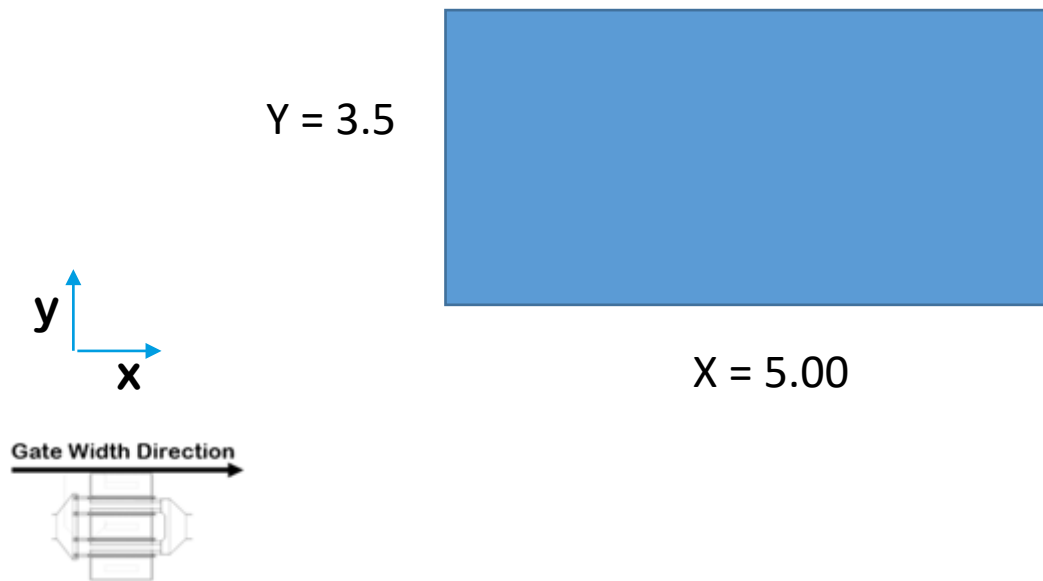
- **MPW Run 3 (GaN09)**
 - 2 mil (50 um) wafer thickness
 - Technology under development (not released)
 - QGaN09 THN PDK will be available through the portal
 - AWR and ADS available
 - No AIC features included

- **MPW Run 4 (GaN15)**
 - 2 mil (50 um) wafer thickness
 - Standard production released GaN technology
 - QGaN15 THN PDK available through the portal
 - AWR and ADS available
 - No AIC features included



Design Space (MPW Runs 3 & 4)

- Each design team will have the following space:
 - **5.00 mm x 3.50 mm***



Reticle will consist of at least

- 3 external designs
- 1 USG design
- 1 Qorvo design
- Plug bar (test structures)

*** Note: The design space size is subject to change if needed based on the design applications received and approved by USG.**



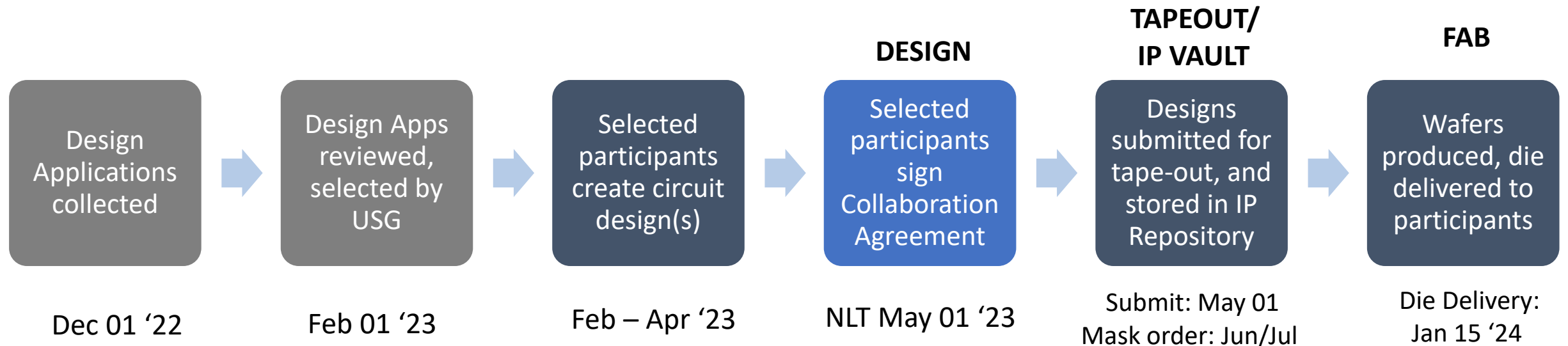
Key Dates for GaN09 and GaN15 Year 2 MPW Offerings

Item	Date	Who
Year2 Design Opportunity Day	Oct 19 '22 - today	USG, SN Performers, Design Applicants
Design Applications Due	Dec 01 '22	Design Applicants
Design Participant Selection	Feb 01 '23	USG
NDA signed	Feb 01 '23	Design Participants
Collaboration Agreement signed	May 01 '23	Design Participants, Qorvo
Design Submissions Due	May 01 '23	Design Participants
Mask Tapeout – Run3/GaN09	Jun 15 '23	Qorvo
Mask Tapeout – Run4/GaN15	Jul 15 '23	Qorvo
Die Delivery – Run3/GaN09	Jan 15 '24	Qorvo
Die Delivery – Run4/GaN15	Jan 15 '24	Qorvo



MPW Run Procedure

- After being selected, Design Participants (“Collaborators”) to sign:
 - **NDA** (required for PDK access)
 - **Collaboration Agreement** (required to be on the mask)
- Collaborators make design, then submit design by deadline in order to have design included in mask





GaN15 & GaN09 - DRC

- Run the **DRC (Design Rule Check)** throughout design effort
 - Do not wait to run DRC until right before deadline!
- DRC is **to be performed via mailtools**
 - Set up a SFTP (secure FTP) account thru Foundry for **mailtools**
 - Different than Year1 - GaN15 & GaN09 will use the same process
- Final design submissions must be:
 - **DRC-clean**
 - **Received by submission deadline (planning for May 01, 2023)**



GaN09 – models, FETs

- New for Year 2 MPWs – GaN09 models and FET cells will be included in the GaN PDK
- These preliminary models will be available by the start of the design period.
- The MPW runs are providing “early access” to unreleased technology. Since the GaN09 process is being refined and matured throughout STARRY NITE, differences between the models and the MPW wafer performance are to be expected.

- GaN09ES THN models & FET cells expected to be available (in AWR & ADS):

Non-Linear Models

- EG3920F, 15V, 25 mA/mm (4ISV)
 - 8 x 50 um

Linear Models

- EG3920 C, G, and F (25C, 85C, -40C)
 - 2 x 25 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (2 End Via)
 - 2 x 40 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (2 End Via)
 - 2 x 50 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (2 End Via)
 - 4 x 25 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (3ISV)
 - 4 x 40 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (3ISV)
 - 4 x 50 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (3ISV)
 - 6 x 25 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (4ISV)
 - 6 x 40 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (4ISV)
 - 6 x 50 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (4ISV)
 - 8 x 50 um: 5V, 7.5V, 10V, 12.5V: (25, 50, 100,200) mA/mm (4ISV)

- Scaling of GaN09 FET cells:
 - The Linear models – likely to be allowed
 - The Nonlinear models – will not be allowed



Services Offered/ Not Offered (for SN MPW Runs)

Offered:

- DC Probe data to check device functionality can be provided by request based on wafer SFC (standard FET cells)
- Die in gel-paks

Not Offered:

- DC, RF probing of MMIC ckts
- Sub-dicing of ckts
- Packaging of ckts



Design IP Repository

- Collaborators' submitted designs will become part of the **STARRY NITE Intellectual Property (IP) Repository**, subject to the Terms of Use set forth by Qorvo and the Government
- STARRY NITE IP storage will be implemented in secure USG-approved Repository. **Access will be USG only.**
- Required items for each submission:
 - Design Layout (GDSII file)
 - Design Schematic (can be encrypted)
 - Document (PPT file) with design info summary (design description, frequency of operation, simulation data, representative measured data)

Q & A



HRL T3 Foundry Overview

STARRY NITE Design Opportunity Day

David Fanning // Harris Moyer // Andy Fu
HRL Laboratories

October 19, 2022

This material is based upon work supported by the Defense Advanced Research Projects Agency (DARPA) under contract no. HR0011-19-C-0006. Any opinions findings and conclusions or recommendations expressed in this material are those of the author(s) and do not necessarily reflect the views of the Defense Advanced Research Projects Agency. (DARPA).

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CUI Category: Distro A – Pending
Distribution/Dissemination Control: A
Distribution Statement (Pending) Public Release





HRL Laboratories agenda



- STARRY NITE Design Opportunity Day

- Overview
- **PDK and designer info**
- MPW and foundry info

Dave Fanning
Harris Moyer
Andy Fu

STARRY NITE PM, SEL
MMIC & RFIC group lead, SEL
Foundry Services Manager, MTL



Understanding GaN T3 Device Performance



- **T3 GaN data sheet**
- **Typical results from a 77 GHz single stage Standard Evaluation Circuit (SEC)**
 - **Comparison with device model**
- **Introduction of new GaN device model '239' with tunable parameters**
- **Comparison of current PDK model ('227') with new '239' model**
 - **Based on 94 GHz load pull data**
 - **Demonstration of how adjustable parameters in the 239 model can tune to fit measured performance**

Presenting new adjustable nonlinear model for use in next generation PDK



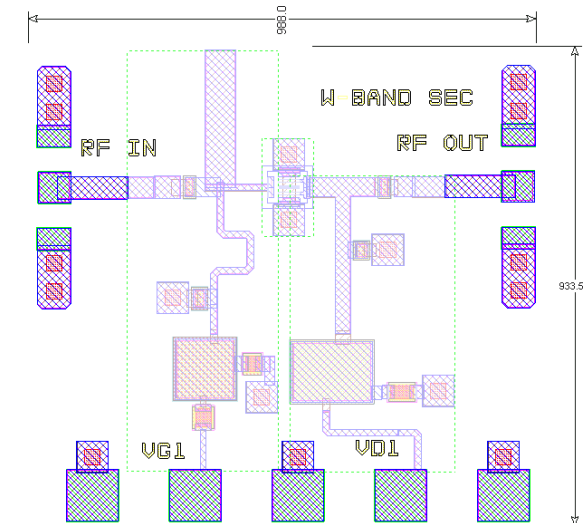
Test Circuit: W-band SEC



- **W-band SEC is a single stage PA centered at 77 GHz**
- **Power was measured at 75,77 and 79 GHz and 12 V @ 100 mA/mm**

Specifications:

Parameter	Lower limit	Median	Upper limit
P1dB (77 GHz)	20.3 dBm	21.8 dBm	23.3 dBm
Psat (77 GHz)	21.5 dBm	23 dBm	24.5 dBm
PAE (77 GHz)	23 %	28 %	33 %
Return loss	6	7.7 dB	10
Small signal gain	6	7.5	9

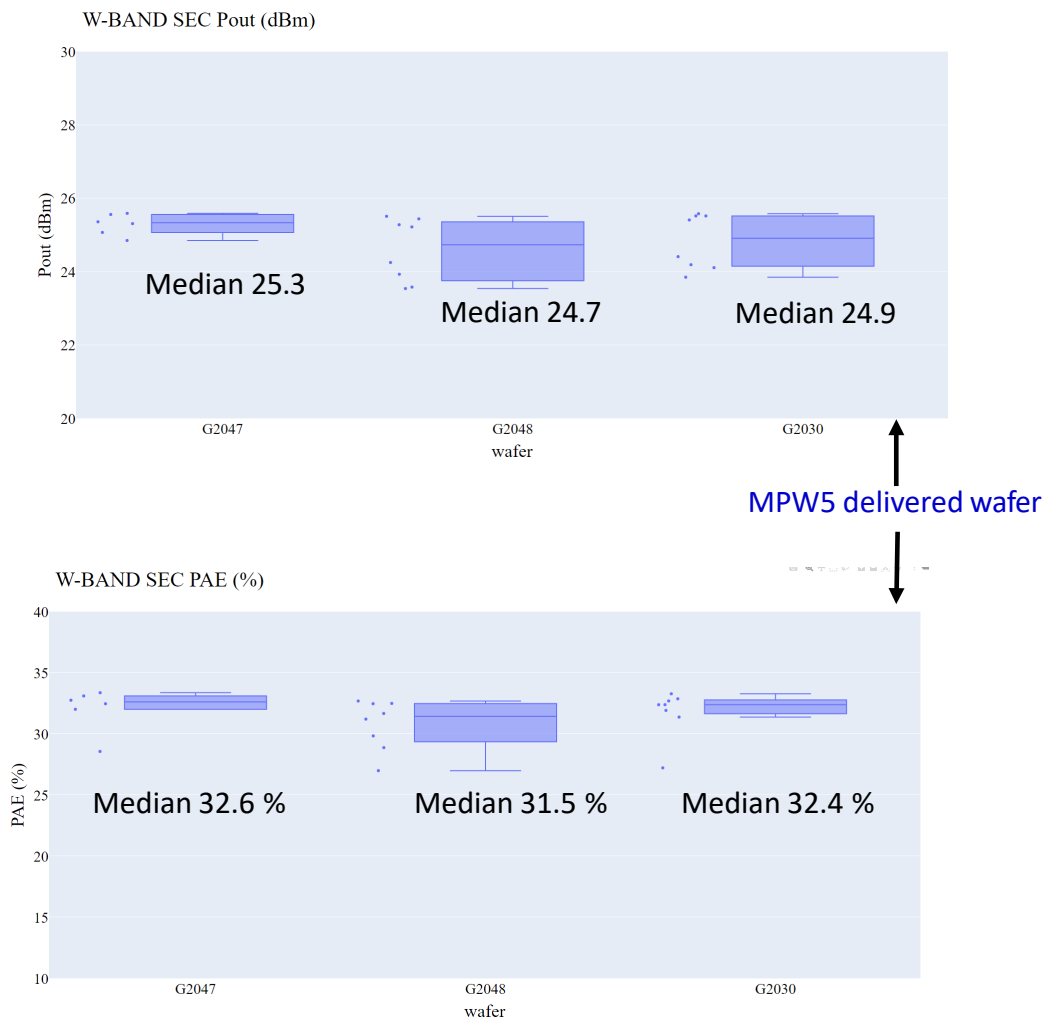




Example of W-band SEC Power results



77 GHz data

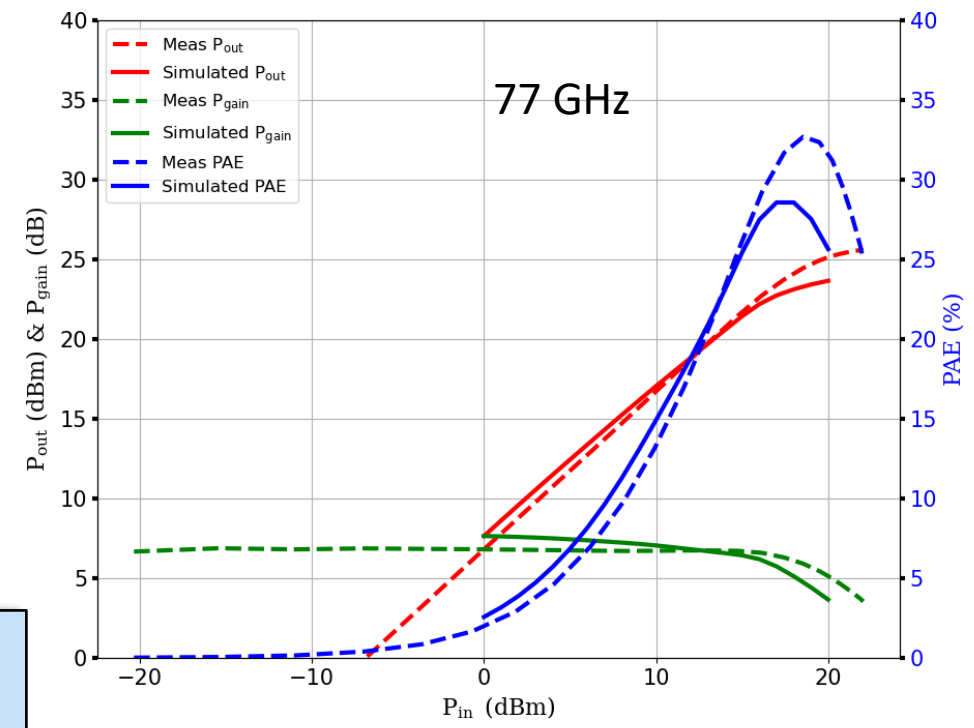
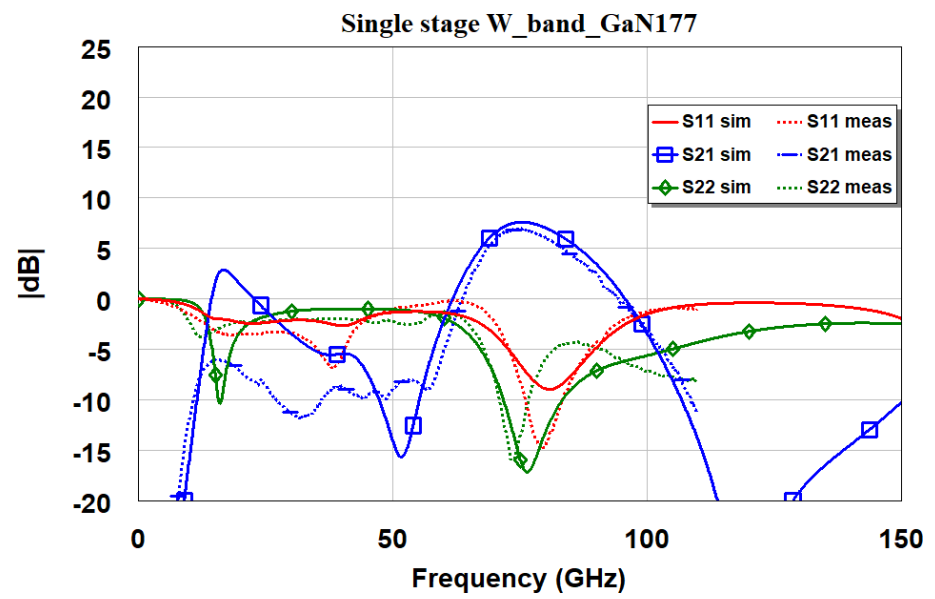


- Measured every W-band SEC on recent MPW5 lot
- Some variation but all of them showed good performance
- Median max PAE \approx 32% across the 3 wafers
- Median output power \approx 24.9 dBm (2.1 W/mm) across the 3 wafers

Represents the high end of expected performance



MPW5 W-band SEC Measured vs. Simulated



- Really good agreement between simulation and measurements!
- Max measured PAE= 33%
- Max Pout= 25 dBm
- Small Signal Gain= 7 dB

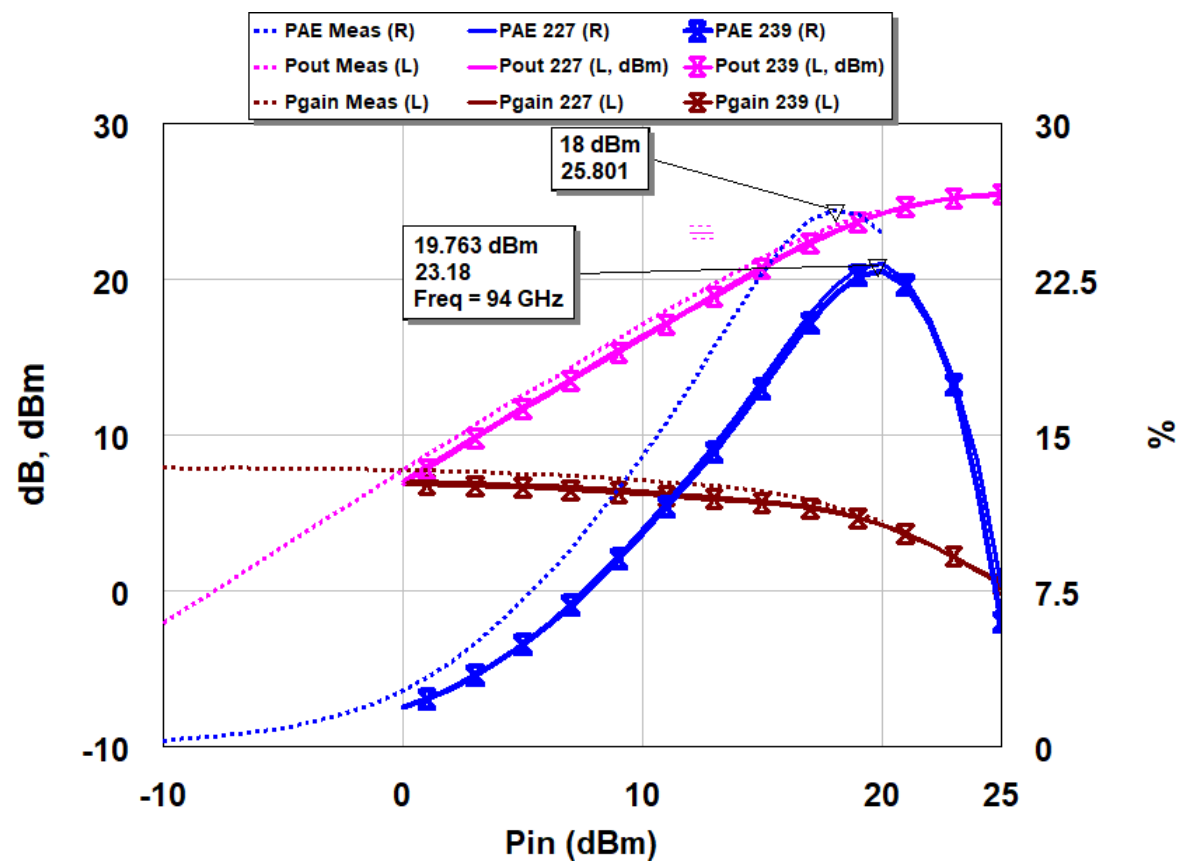
Model used is GaN T3 model ('227') from current PDK which cannot be modified



Measured vs. Simulated load pull power sweep at 94 GHz 4x37.5 μ m

Measured data from load pull at 94 GHz

Bias: 12 V, 15 mA (100mA/mm)
 $Z_{source} = .69 \angle 172^\circ$
 $Z_{load} = .55 \angle 119^\circ$
Input and output harmonics
 $Z = 0 \angle 0$



Both 227 and 239 (default) models have reasonable agreement with measurements



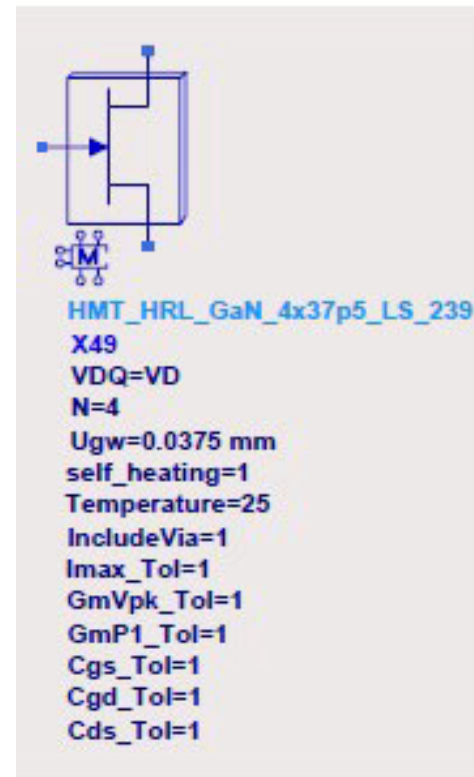
New 239 Model has six Adjustable Parameters



Parameters are based on the % of the nominal model value: +/- 50% (0.5 to 1.5)

Most important parameter is I_{max} which adjusts for variation in current collapse:
Important for power amplifier designs

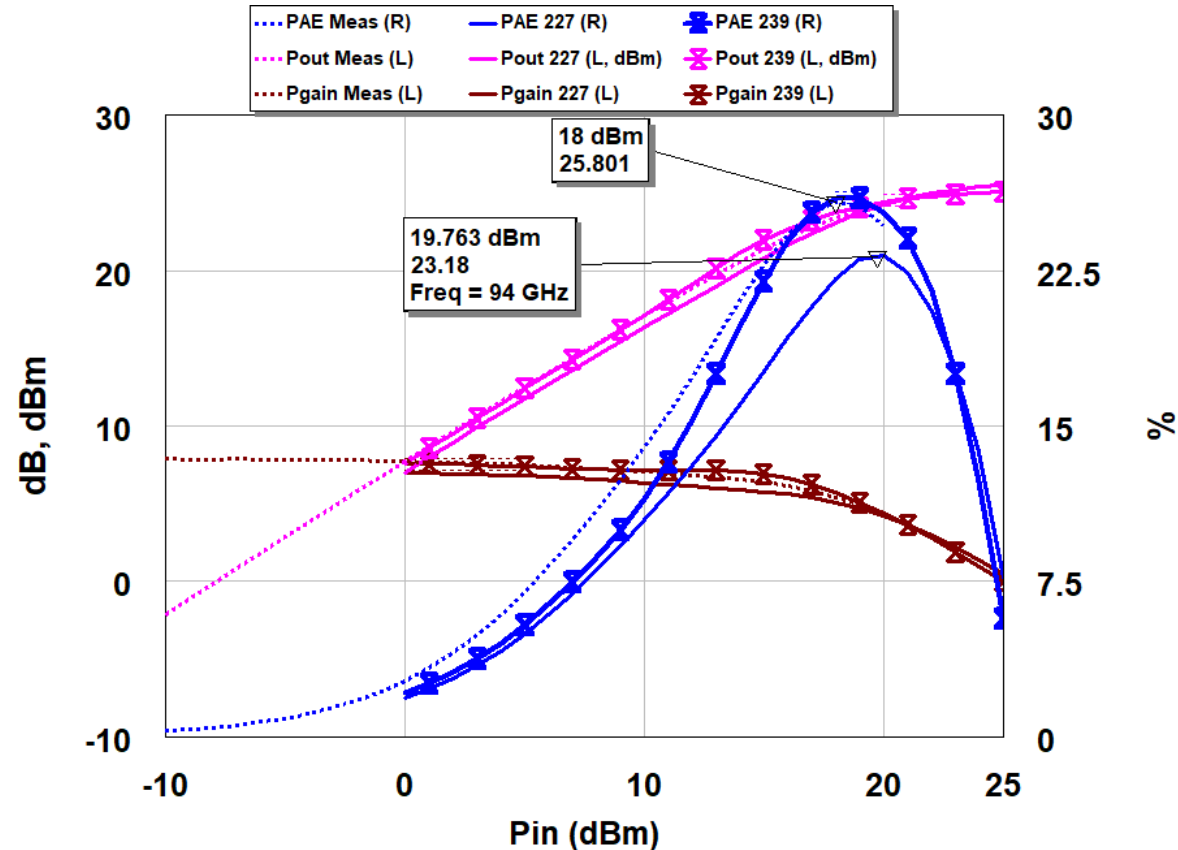
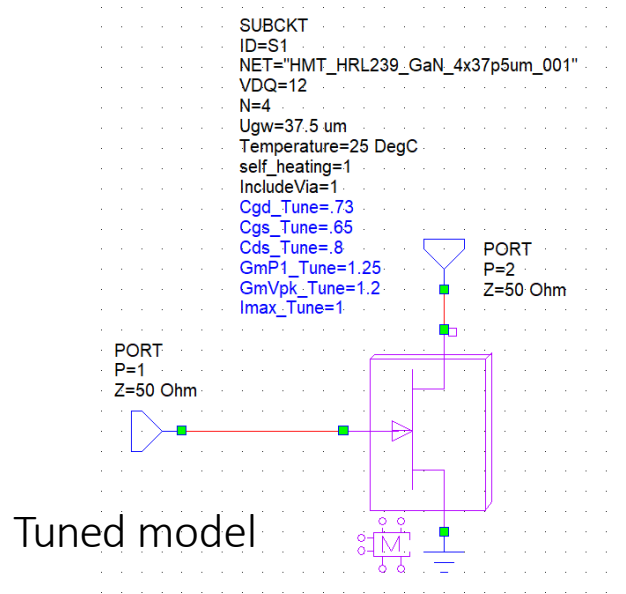
Also includes variable g_m and a g_m shaping parameter



New 239 model has adjustable parameters to simulate process variations

Adjust 239 Model to Match Measured Performance

Measured data from load pull at 94 GHz (AFRL)



The tuned 239 model has excellent agreement with measurements



Near term plans

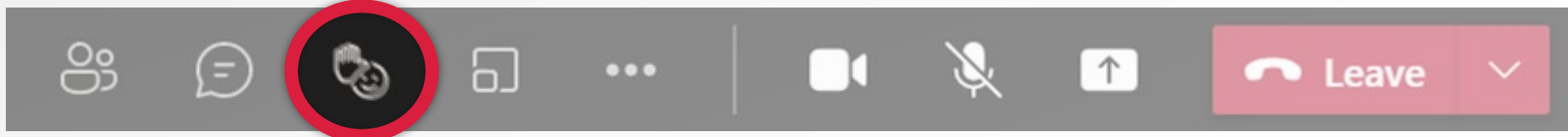
- Upgrade PDK (current version is 1.0.4.4) in both Cadence AWR and Keysight ADS
 - Incorporate new 239 model
 - Correct small layout errors in passive devices
 - Add LVS capability to Keysight ADS
- HRL is adding W-band load pull capability
 - Will allow for model verification
 - Have added a new SEC to verify performance in the 90-95 GHz band
- Work on better understanding process variations to enable accurate Monte Carlo simulations
 - Add more variable parameters to model
 - Better understanding of parameter variation



Questions?

Virtual Audience:

Please use the Raise Hand feature to ask a question





Thank you for joining!



Doug C.

S²MARTS Director
doug@nstxl.org



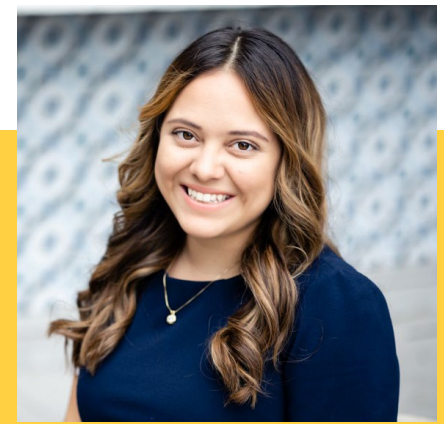
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